

Damage to optics under irradiations with the intense EUV FEL pulses

Ryszard Sobierajski¹, Eric Louis²

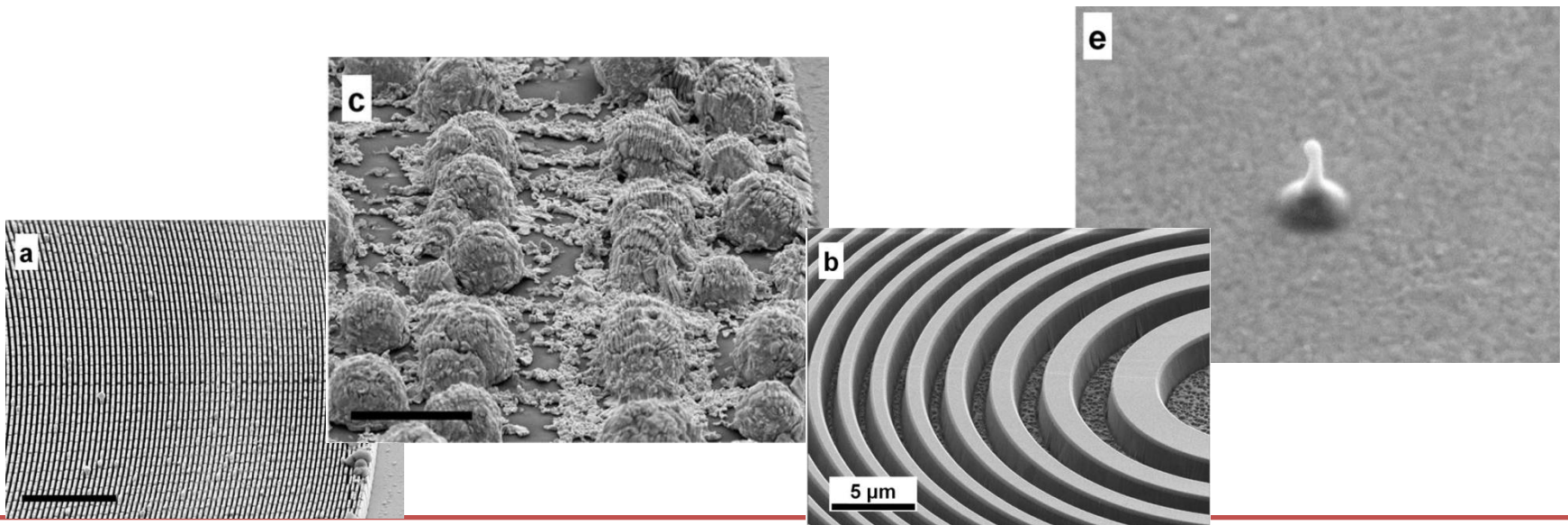
¹*Institute of Physics PAS,*

²*Universiteit Twente*

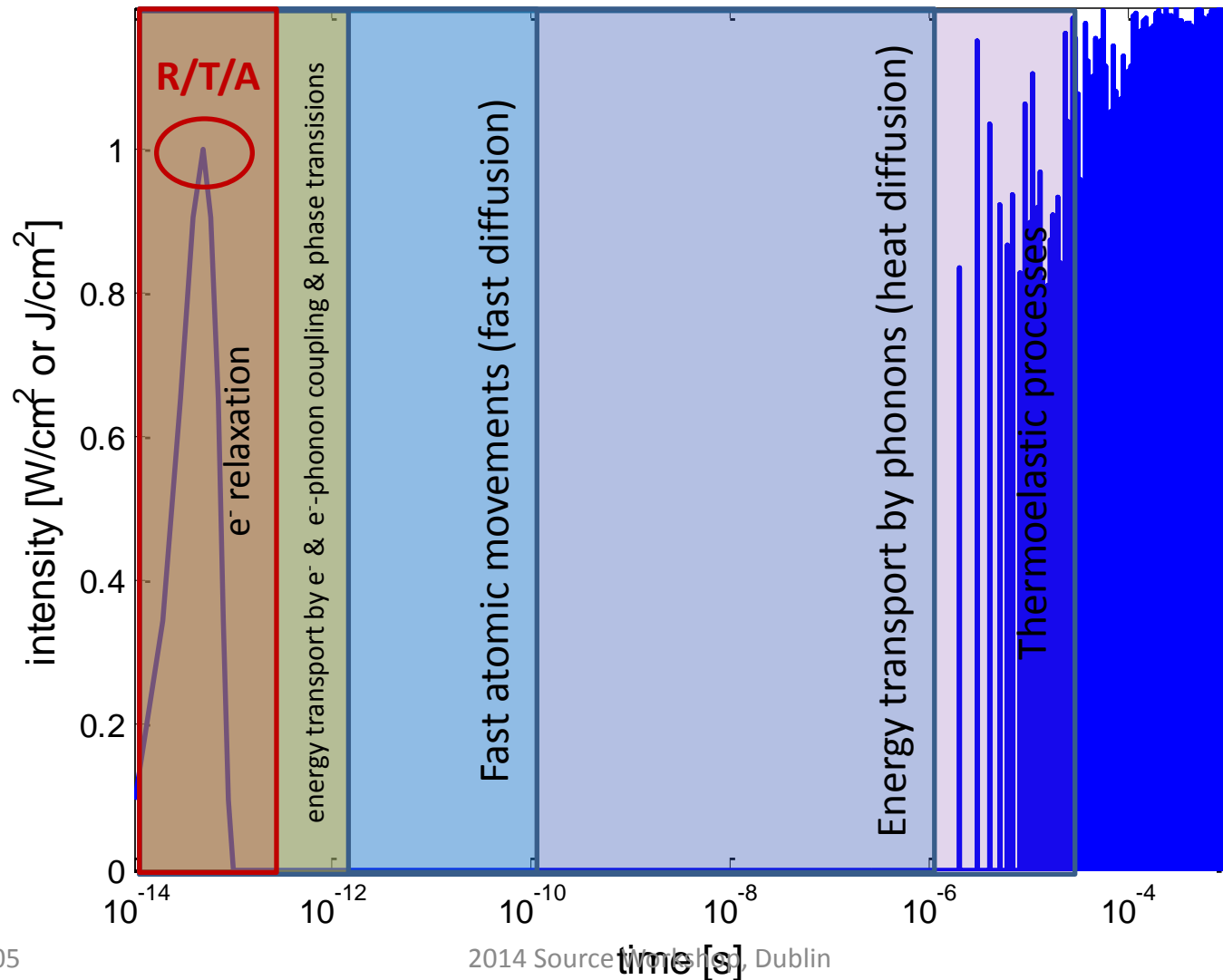
Damage to optics - motivation

Properties of the intense FEL beam create, apart new experimental opportunities, extreme demands to optical elements applied in the experimental equipment. Amongst the most serious issues is **radiation load** imposed on of **optics / detectors / samples**.

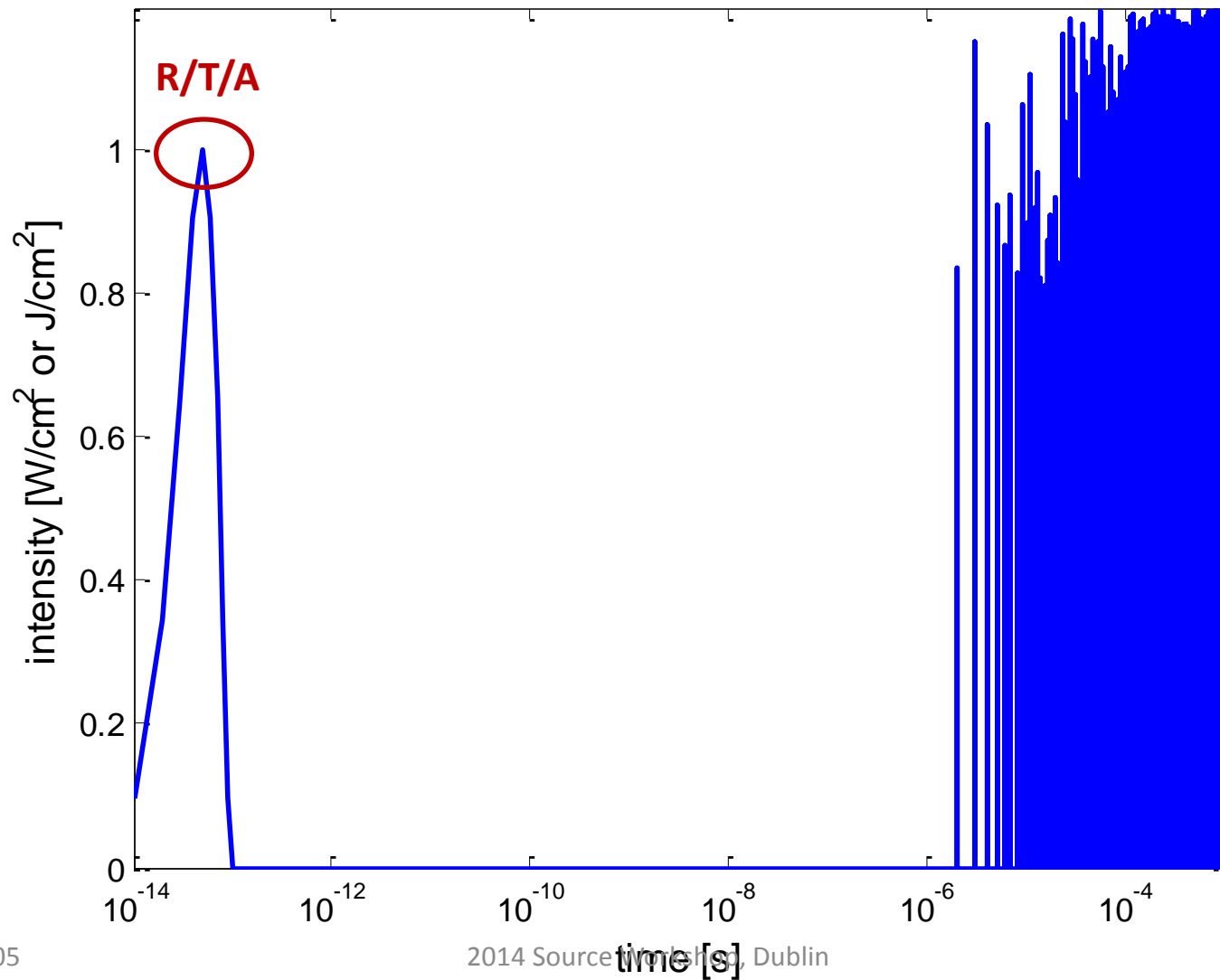
C. David et al. Scientific Reports Vol. 1, (2011)



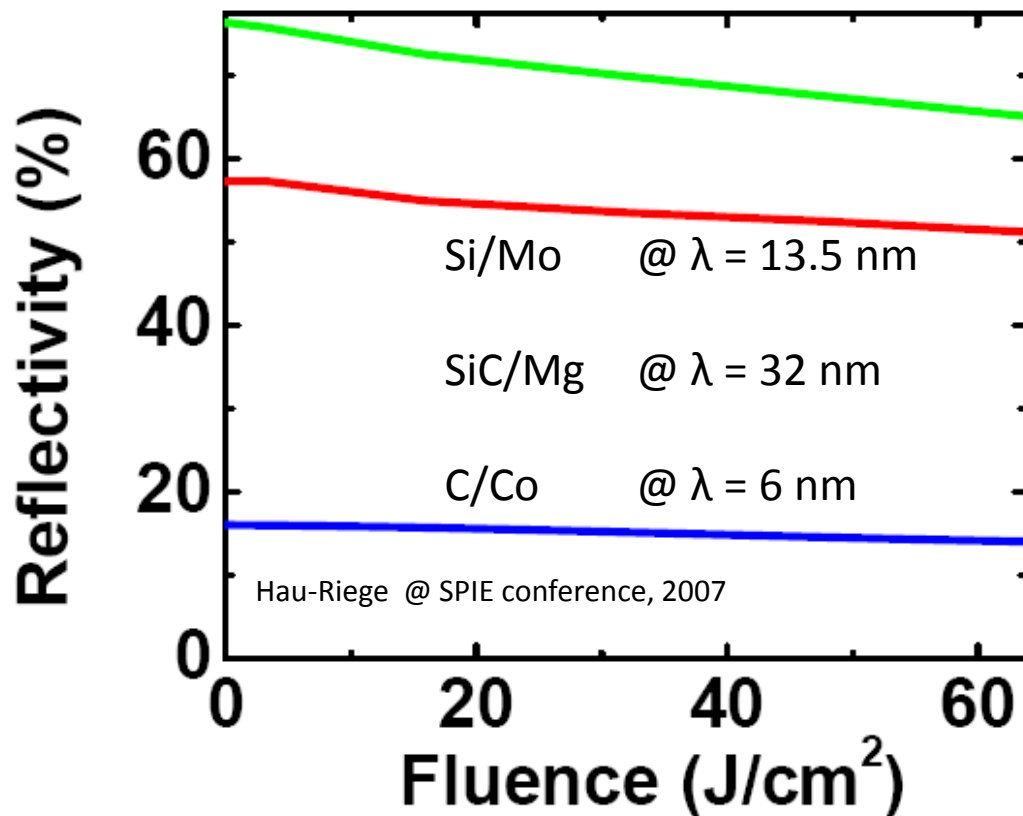
Characteristic times & processes



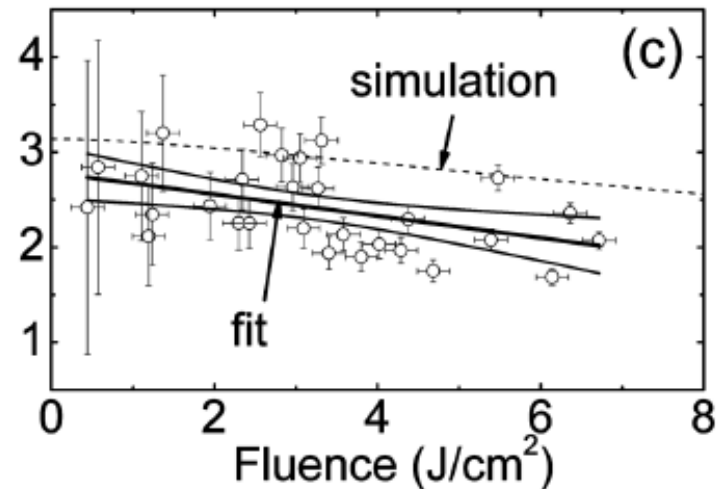
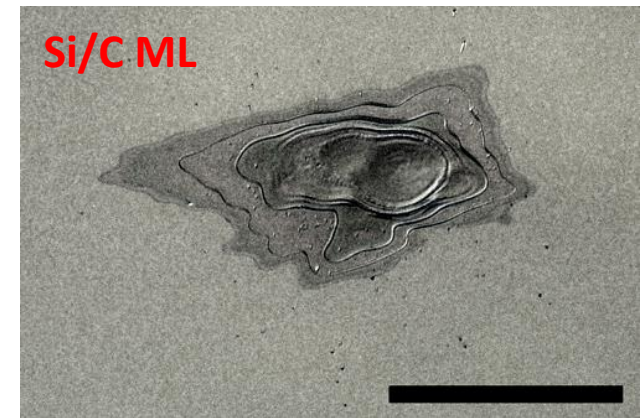
Characteristic times & processes



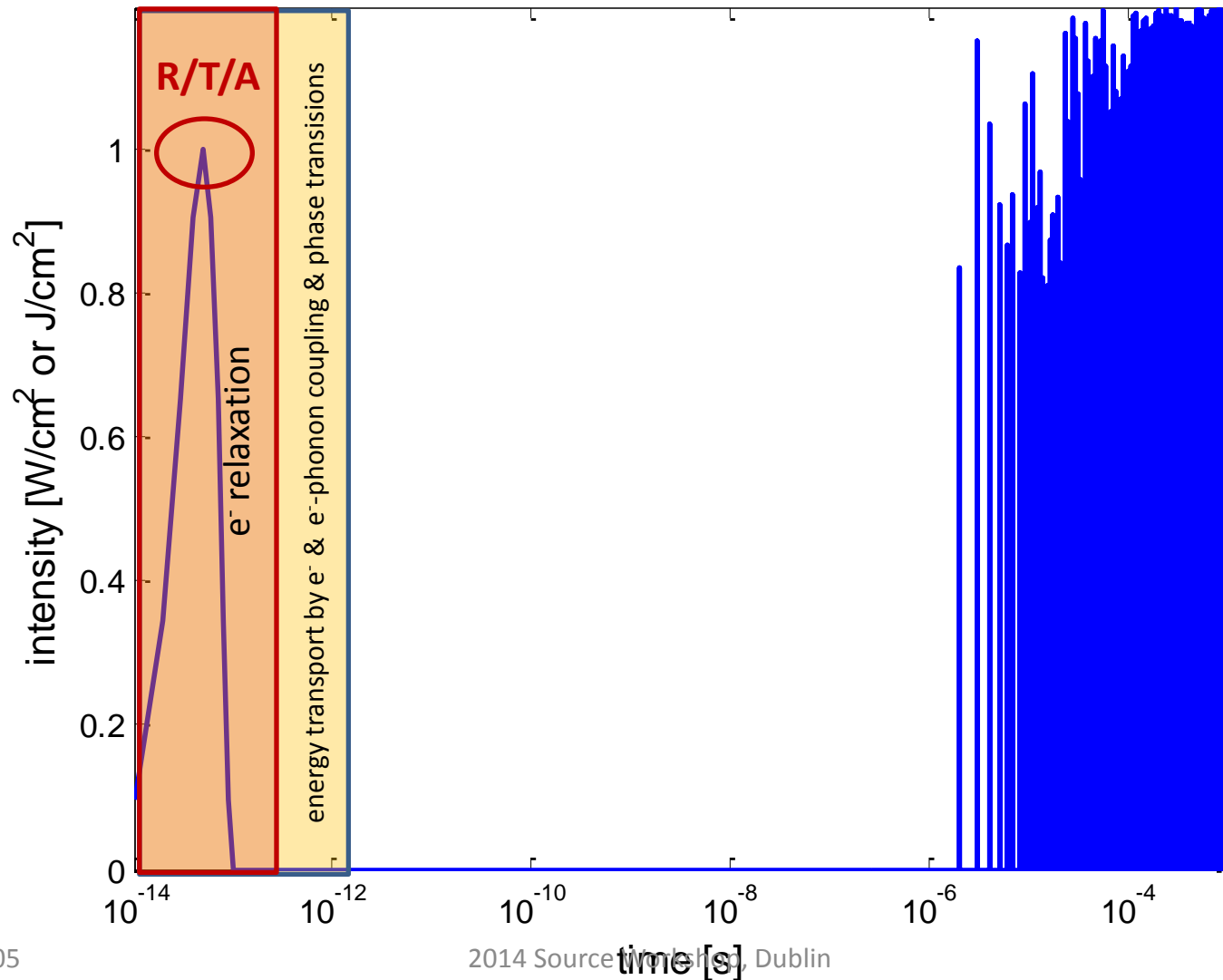
Intensity-dependent changes of optical properties – „single shot” optics



S.Hau-Riege, R.Sobierajski, PRL 98, 145502 (2007)

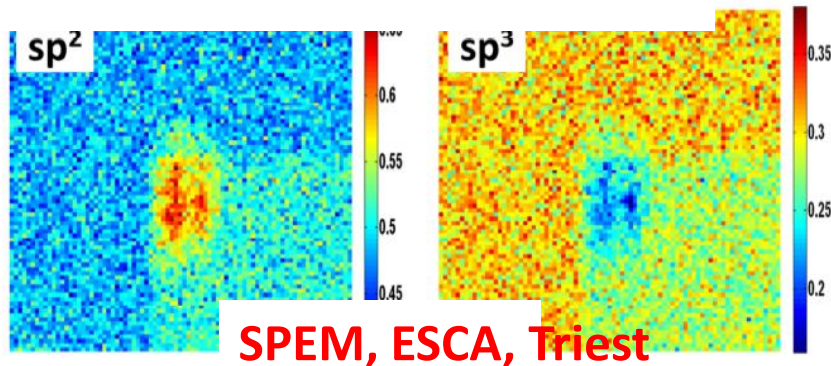
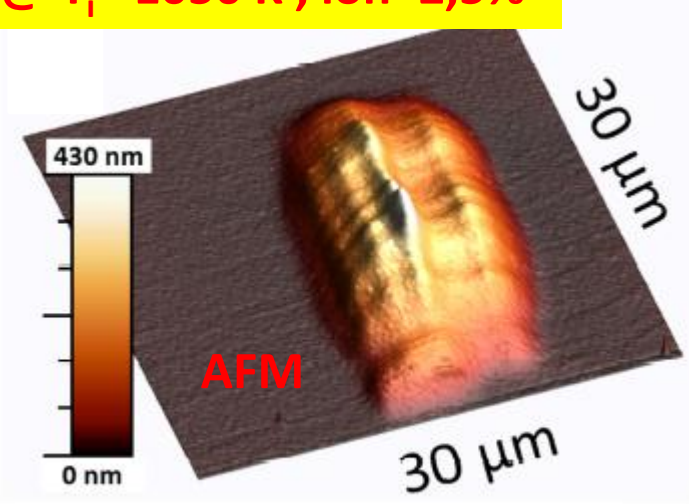


Characteristic times & processes

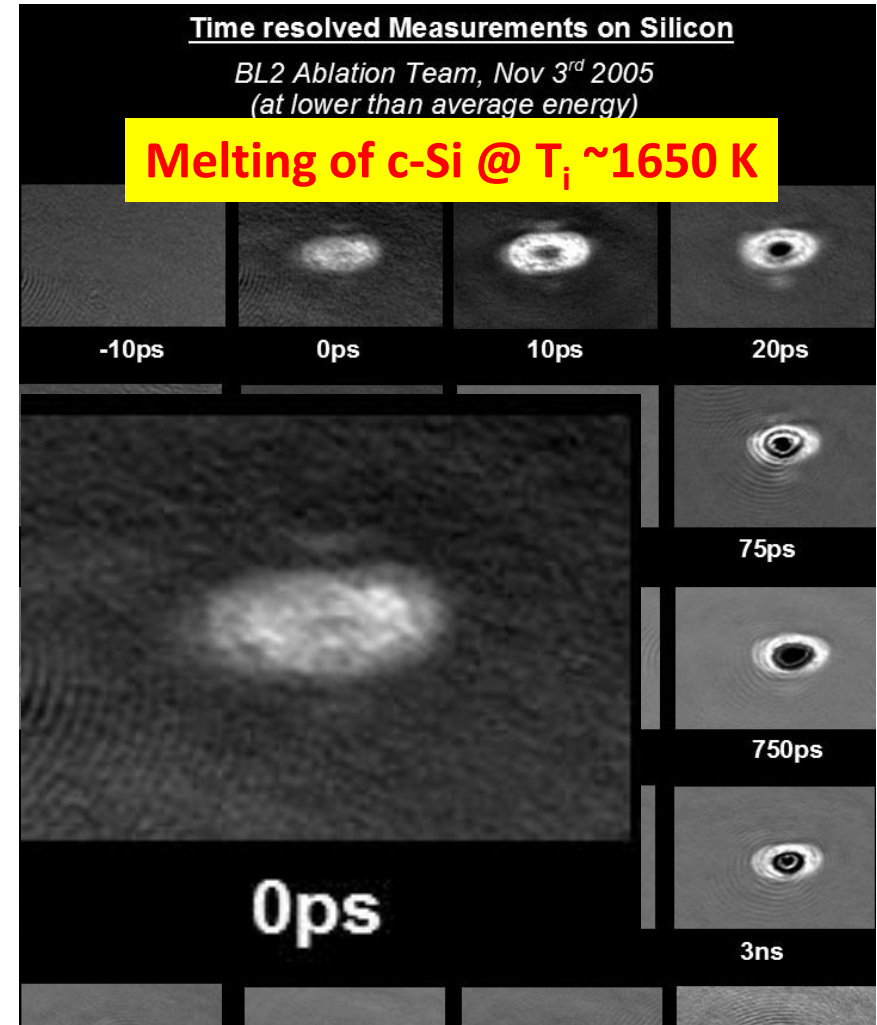


Phase transitions (s-s & s-l)

**Graphitisation of a-C
@ $T_i \sim 1050$ K, ion $\sim 2,5\%$**

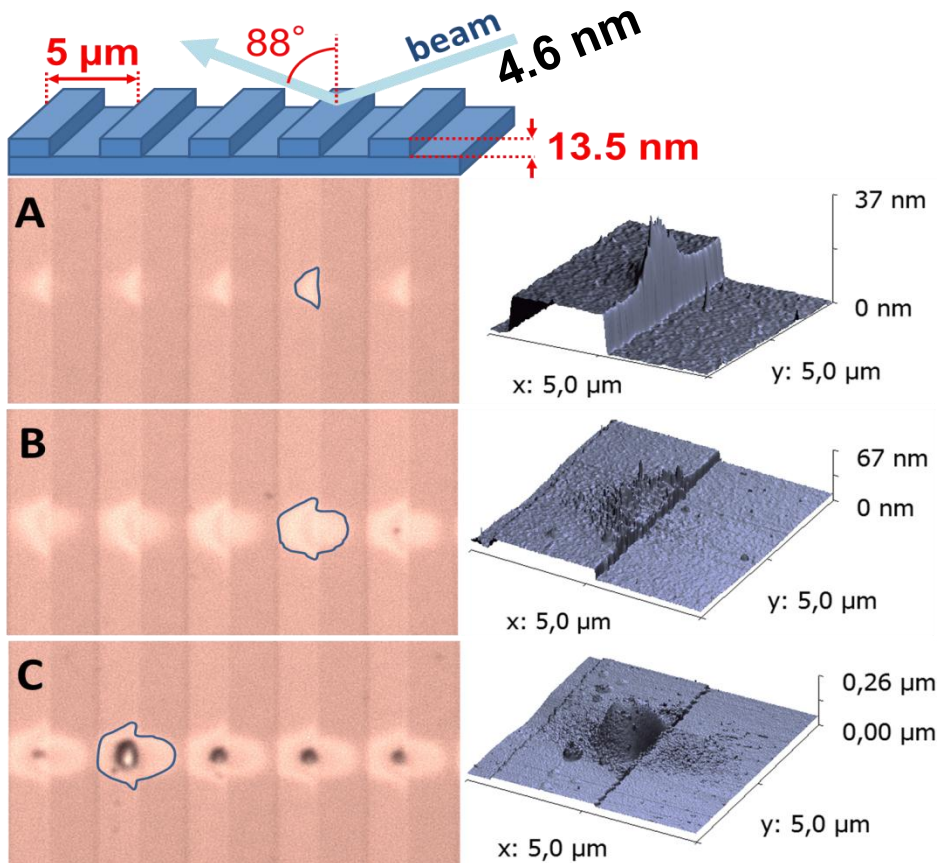


*J. Gaudin et al.,
Physical Review B 86 p.024103 (2012)

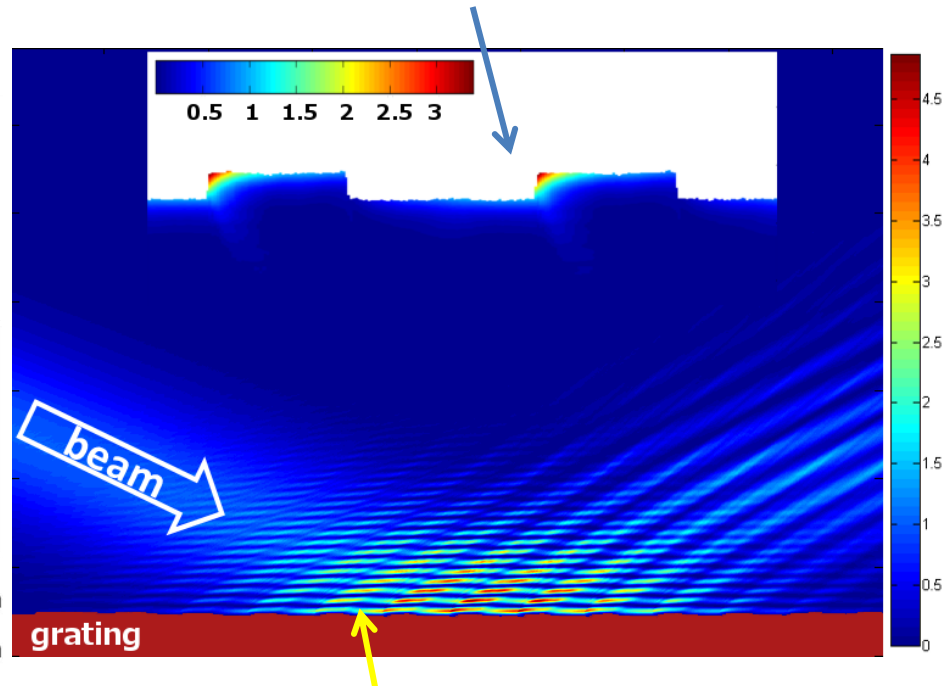


*N. Stojanovic et al.,
Appl. Phys. Lett. Vol. **89**, s.241909, (2006)

Thin (a-C) layers on gratings



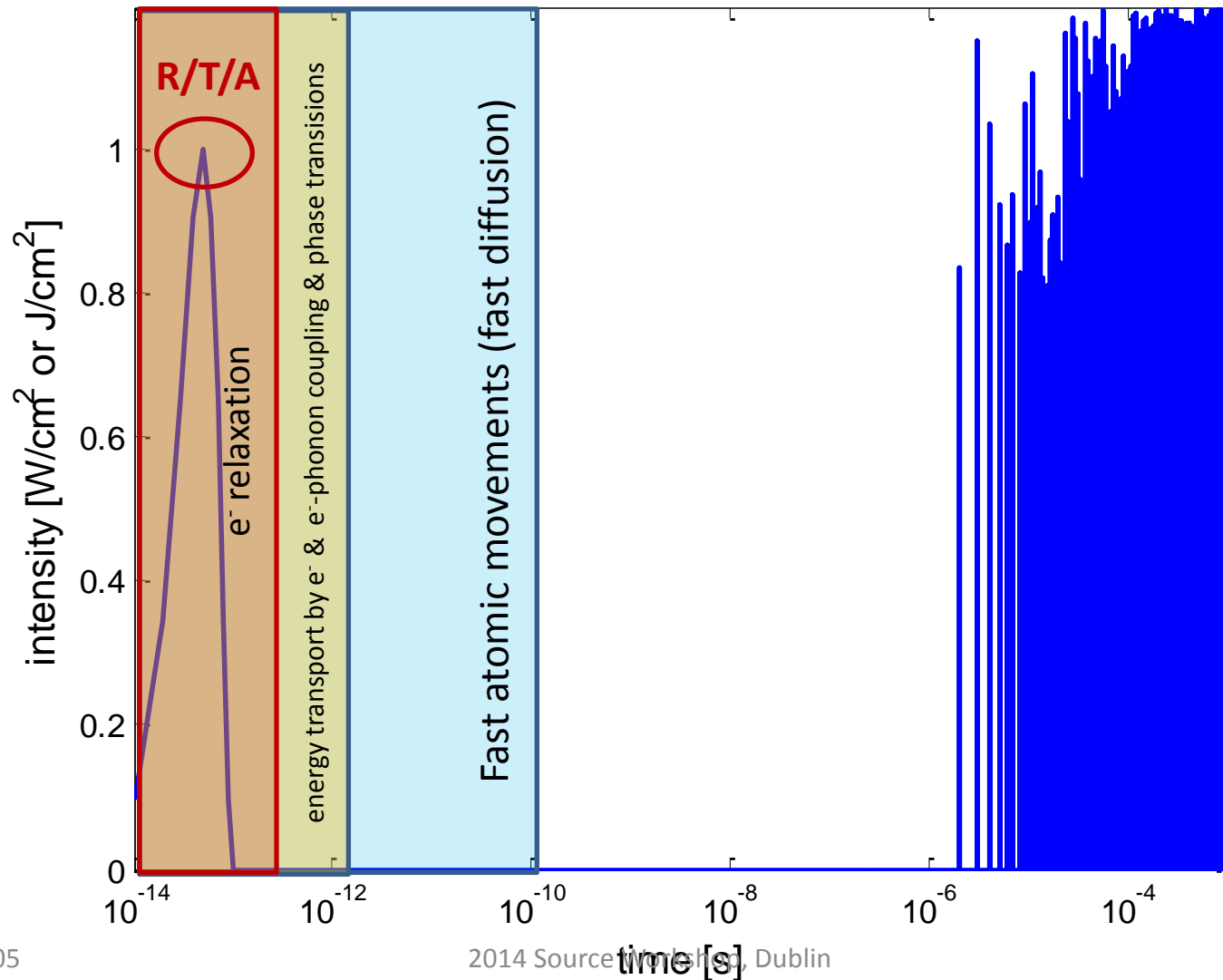
Energy distribution absorbed in the grating



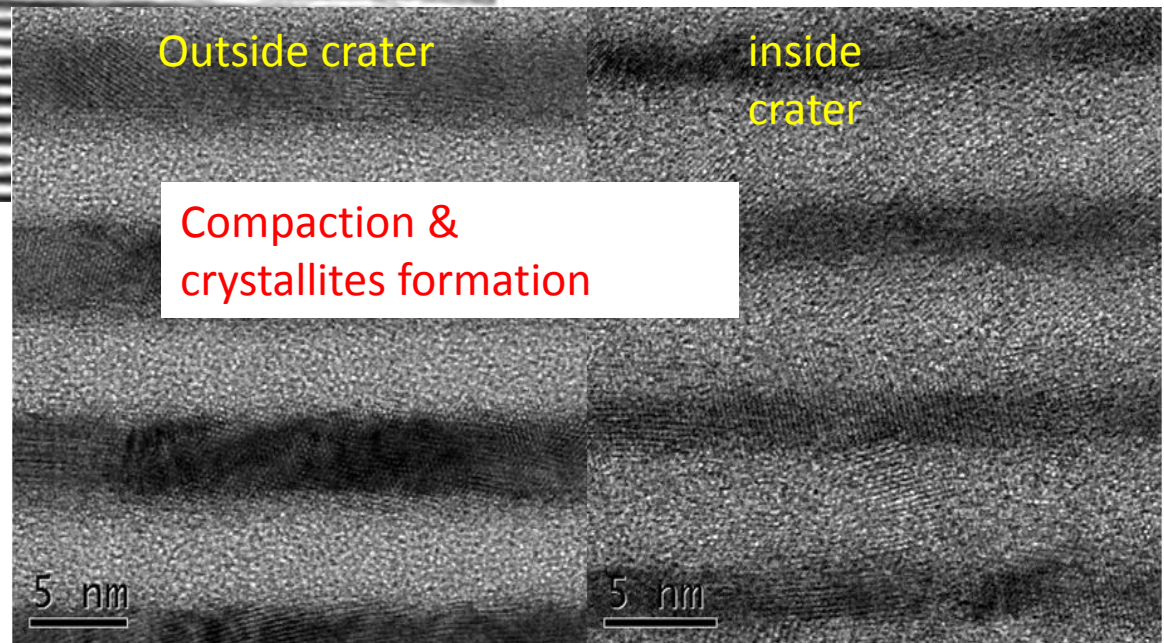
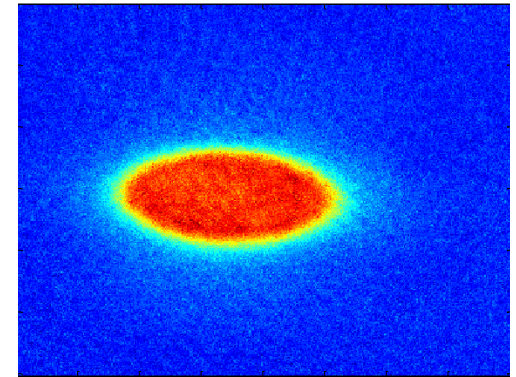
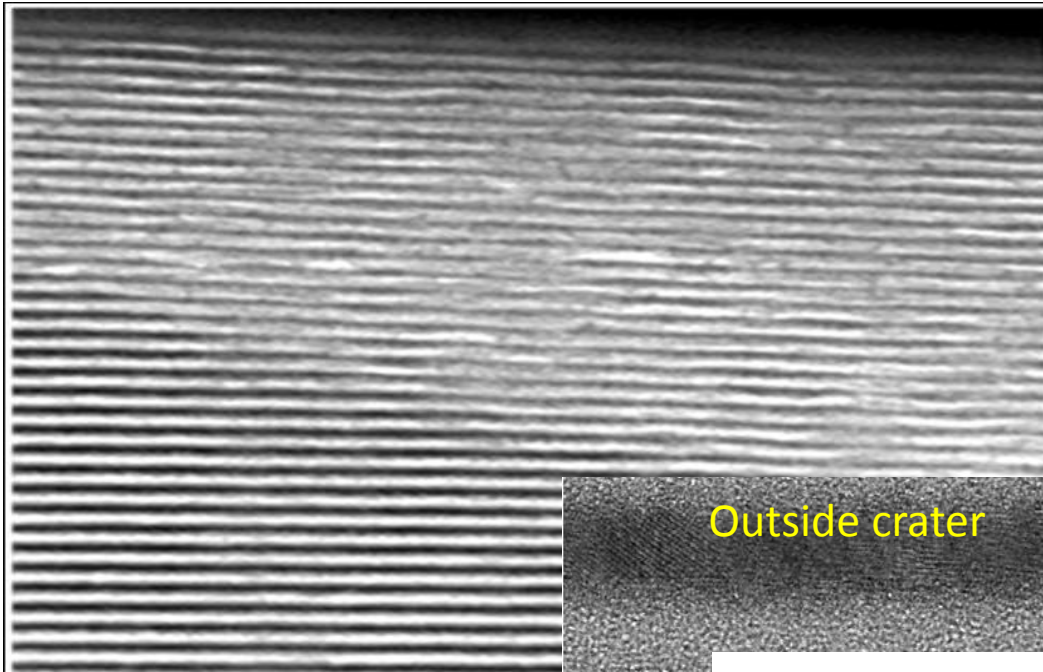
Simulations of the X-ray intensity distribution based on solution of the Helmholtz equation

*J. Gaudin et al.,
Opt. Lett 37 p.2022 (2012)

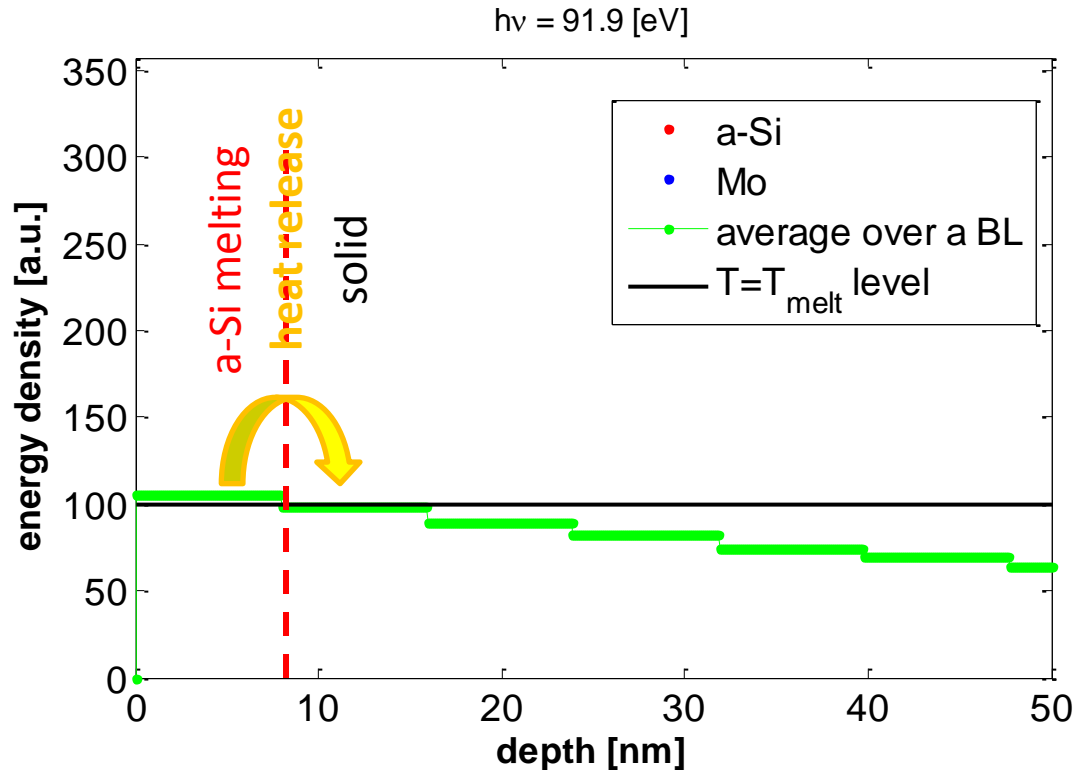
Characteristic times & processes



Atomic diffusion in multilayer Mo/Si coating ($h\nu \sim 92\text{eV}$)



Single shot damage in Mo/Si ML - model

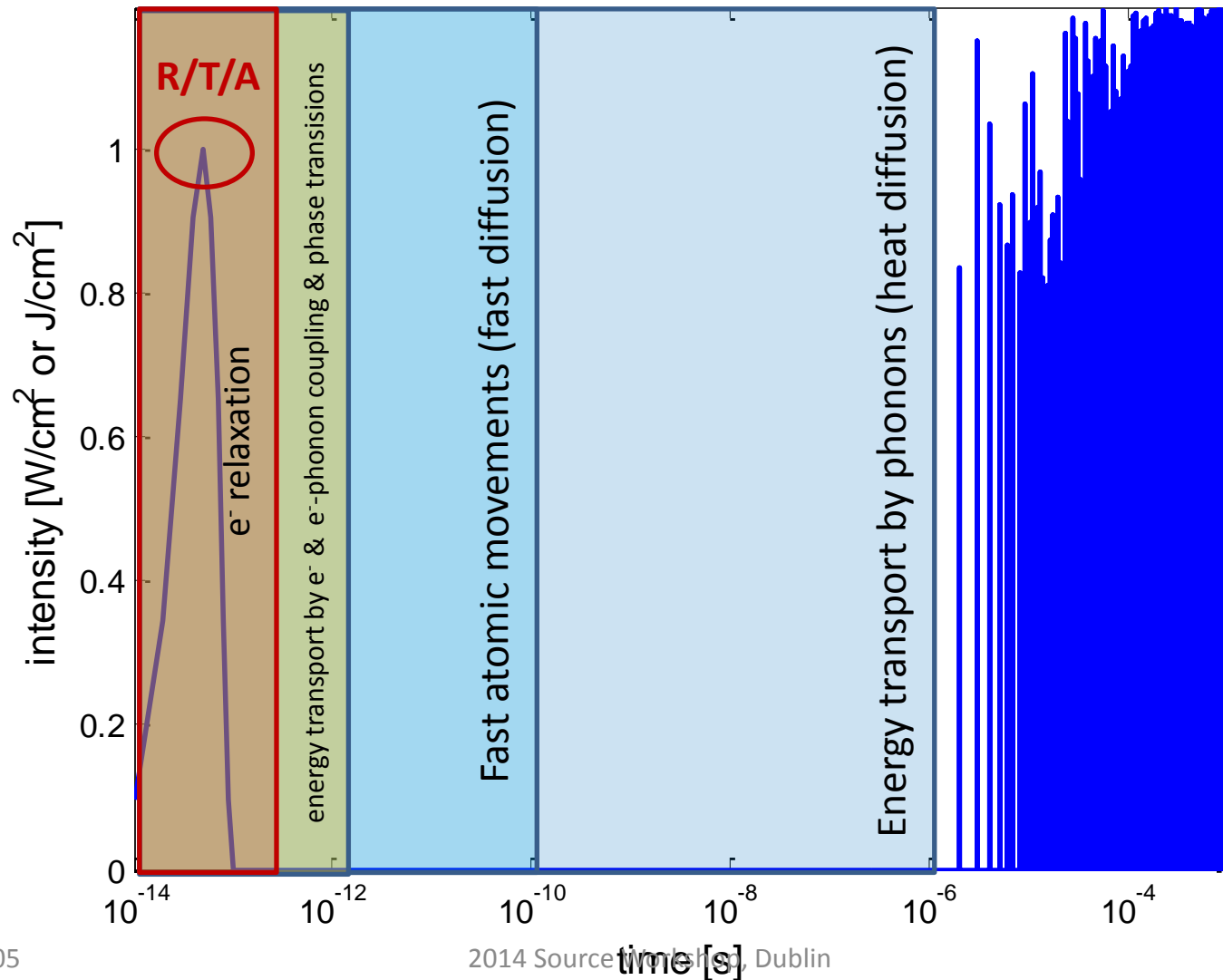


A.R. Khorsand, R. Sobierajski, et al.
Optics Express 18, s.700 (2010)

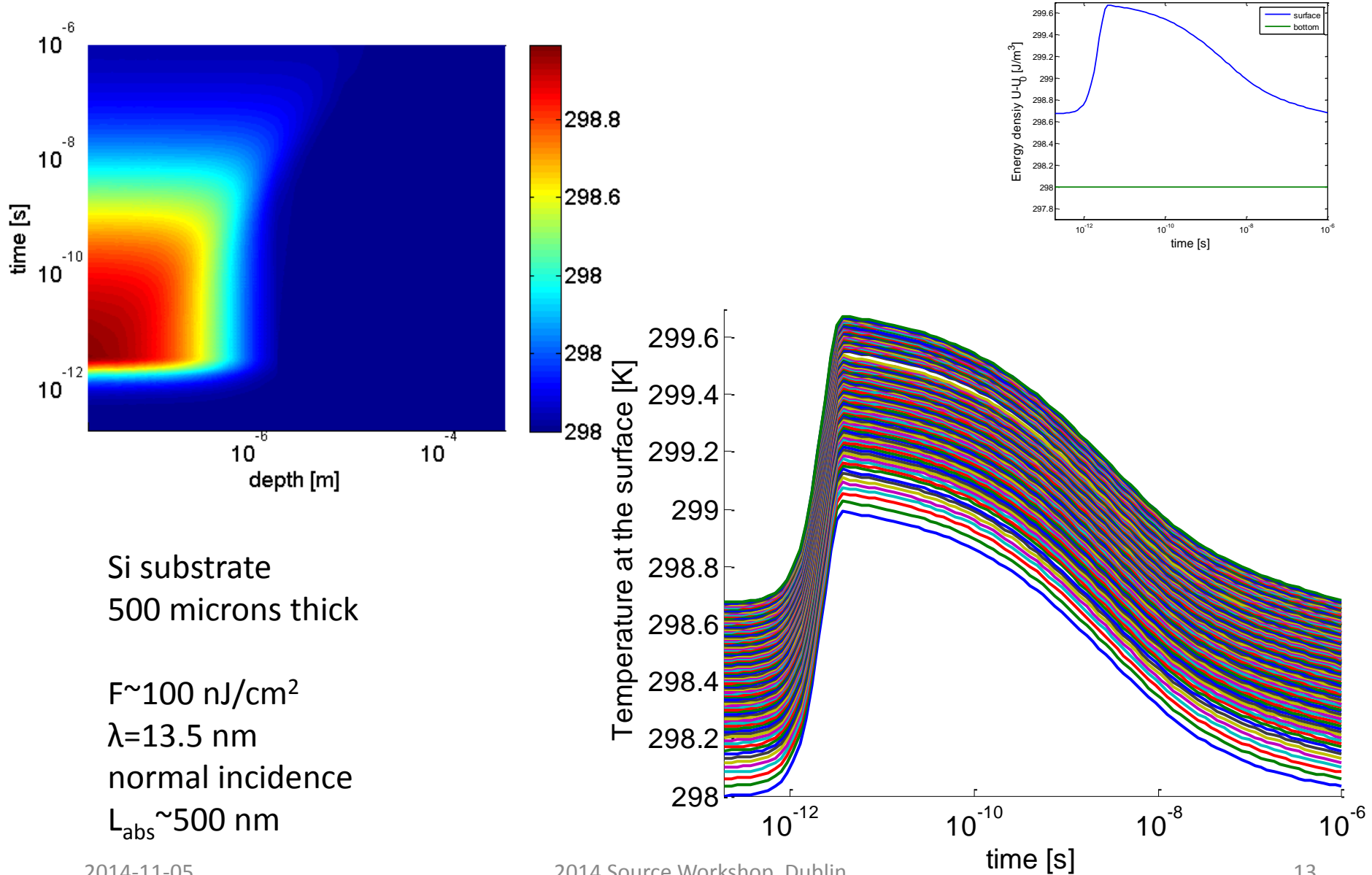
Damaging mechanism identified:

- *energy absorption*
- *energy diffusion transfers heat from Mo layers to a-Si*
- *melting of Si layers enables fast diffusion of Mo atoms into Si*
- *self-sustained reaction due to reaction heat release*
- *period compaction for bilayers with melted a-Si → crater formation*

Characteristic times & processes

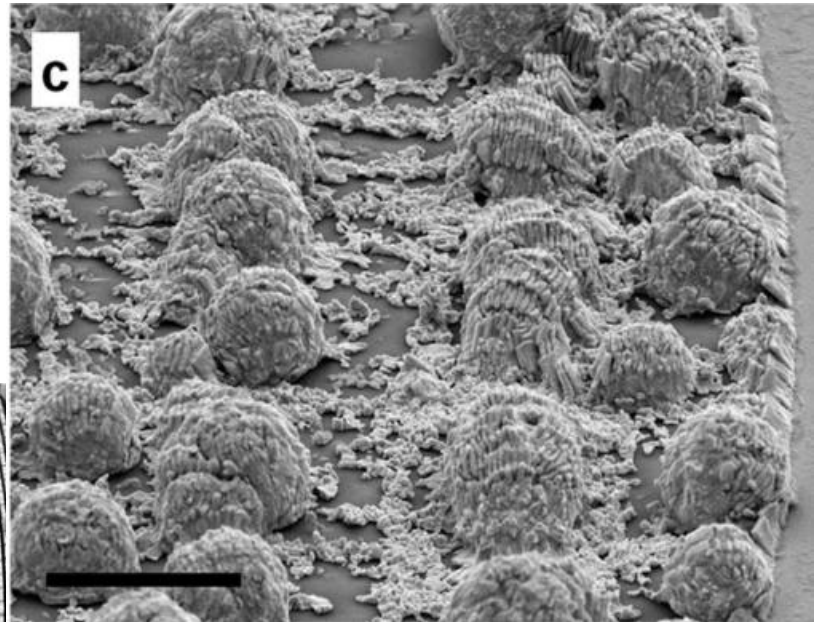
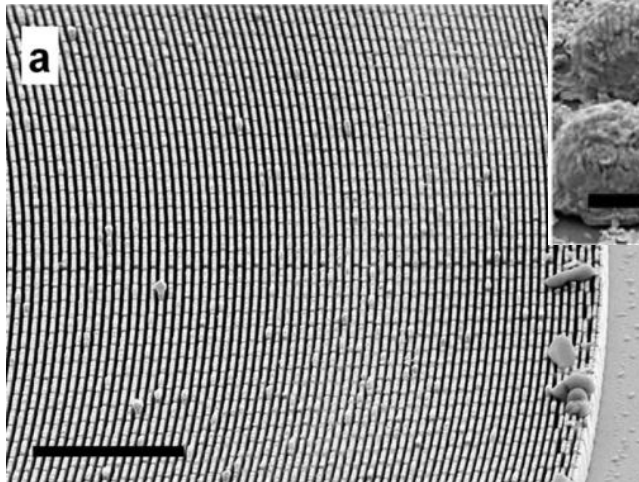


Heat diffusion by phonons & heat accumulation

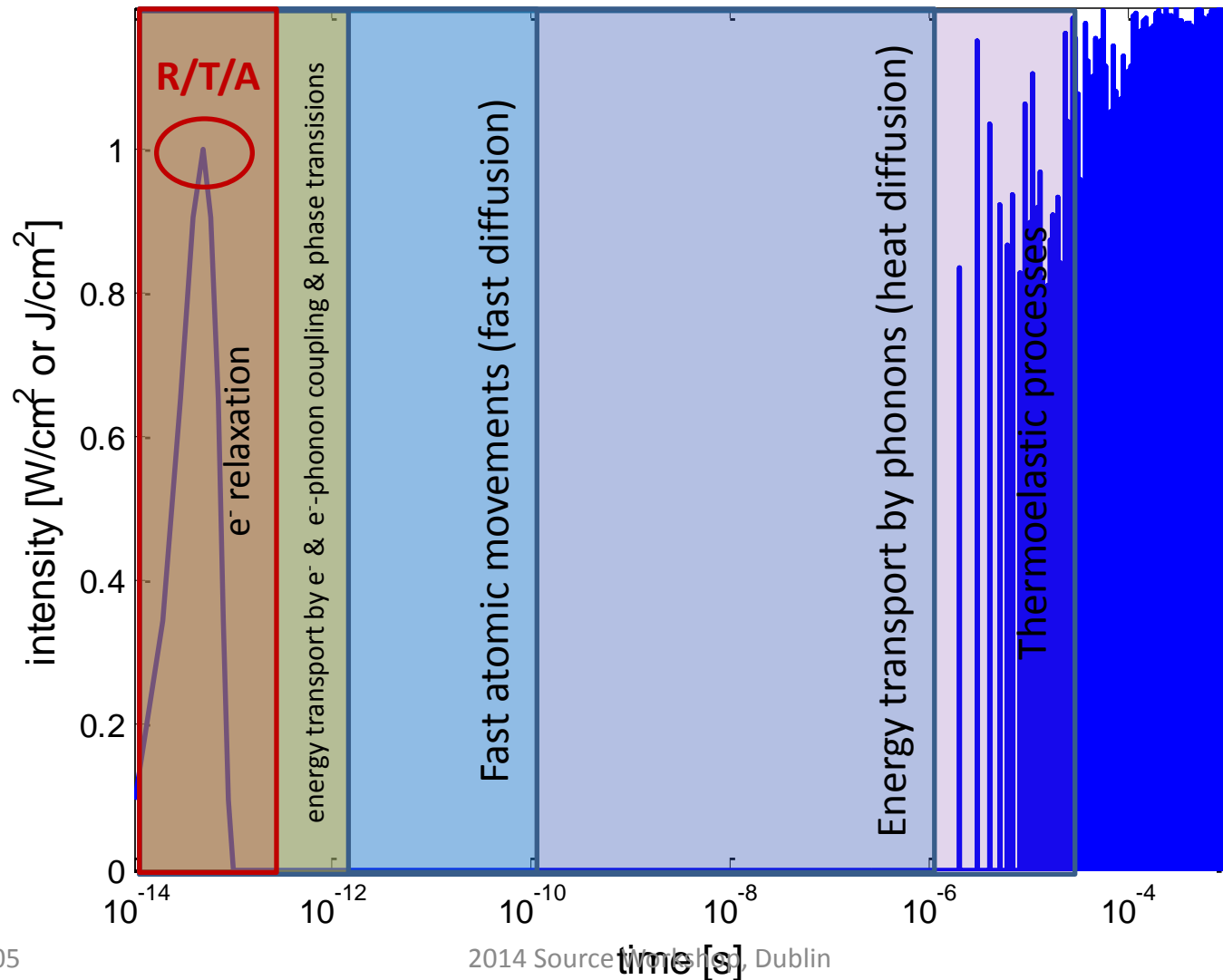


Heat accumulation effects - melting

C. David et al. Scientific Reports Vol. 1, (2011)



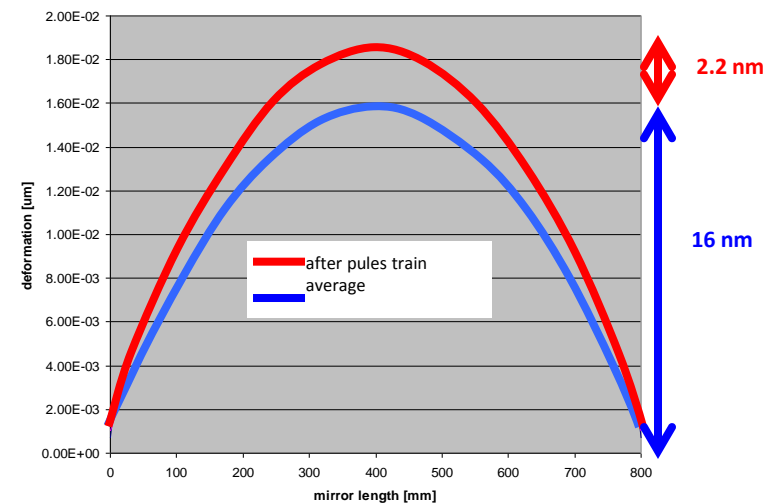
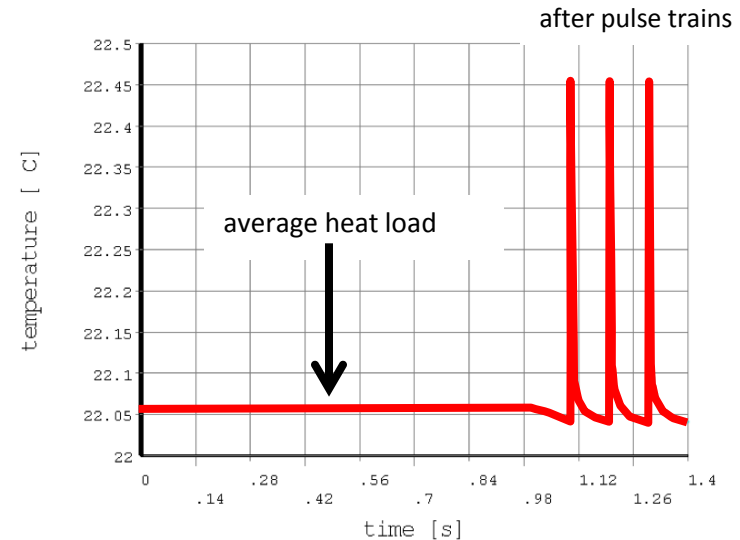
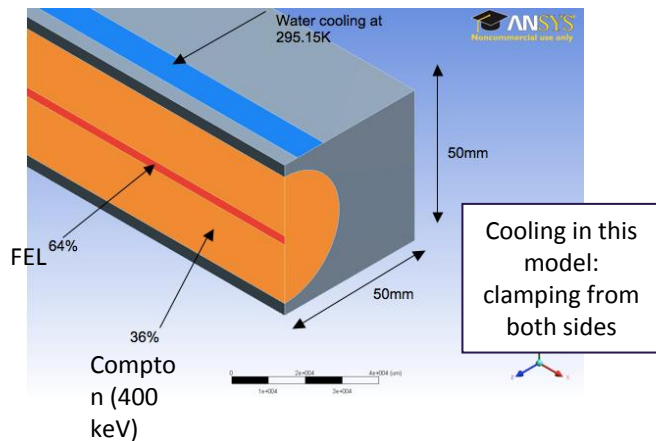
Characteristic times & processes



Heat load distribution on first mirror SASE1 @ Eu-XFEL

17.5 GeV,
13500 pulses per second

Slide courtesy H.Sinn
from X-ray optics CDR on xfel.eu (2011)



Time-resolved studies of the deformations

REVIEW OF SCIENTIFIC INSTRUMENTS

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Thermal stresses in the reflective x-ray optics for the Linac Coherent Light Source

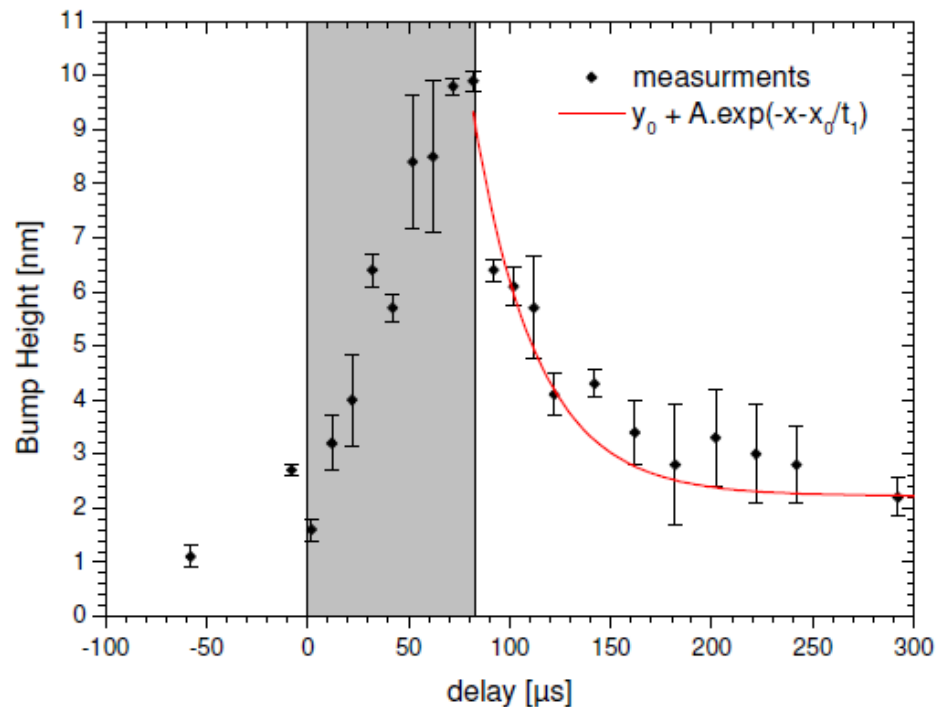
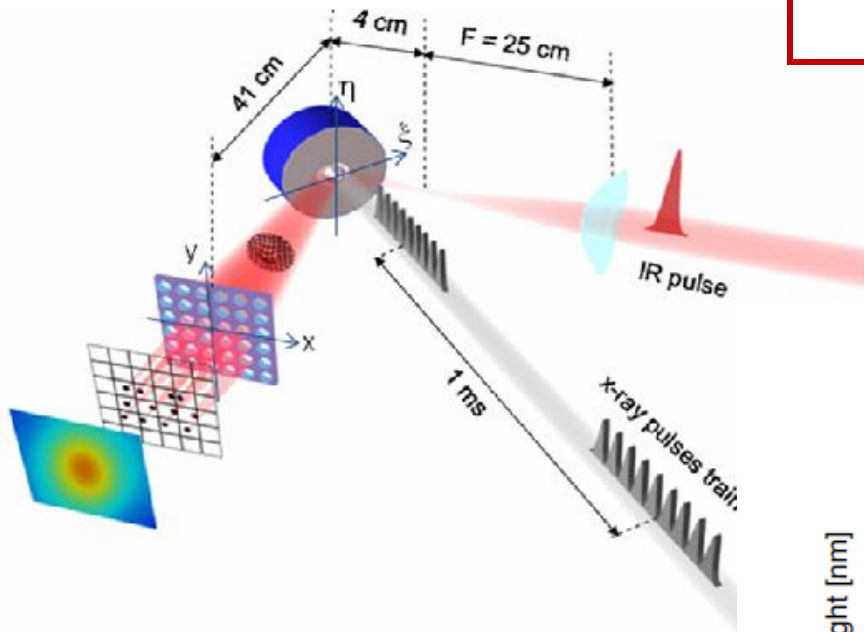
D.D.Ryutov

D. D. Ryutov^{a)}

Lawrence Livermore National Laboratory, Livermore, California 94550

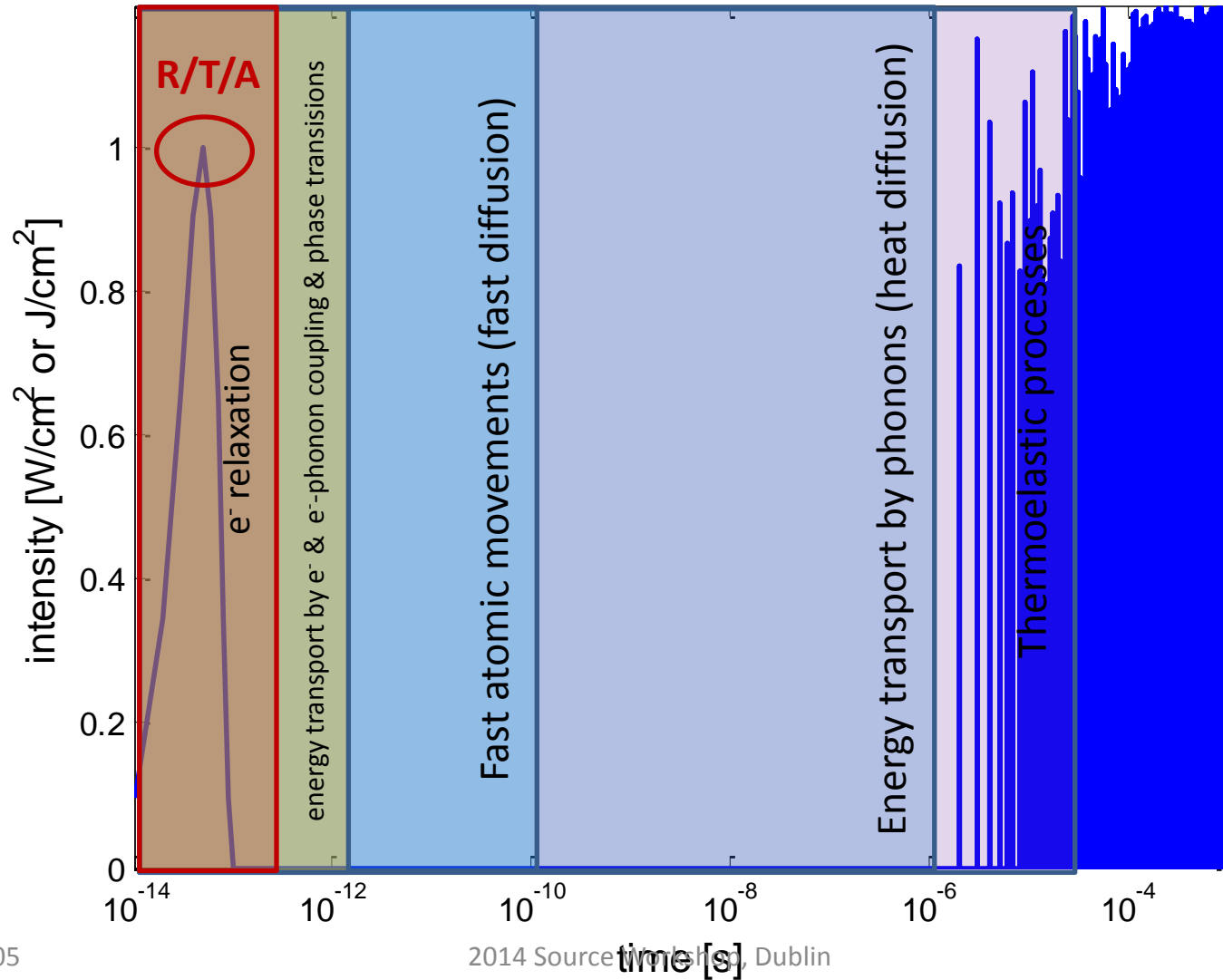
(Received 21 January 2003; accepted 14 May 2003)

Rev. Sci. Instr. 74 (2003)



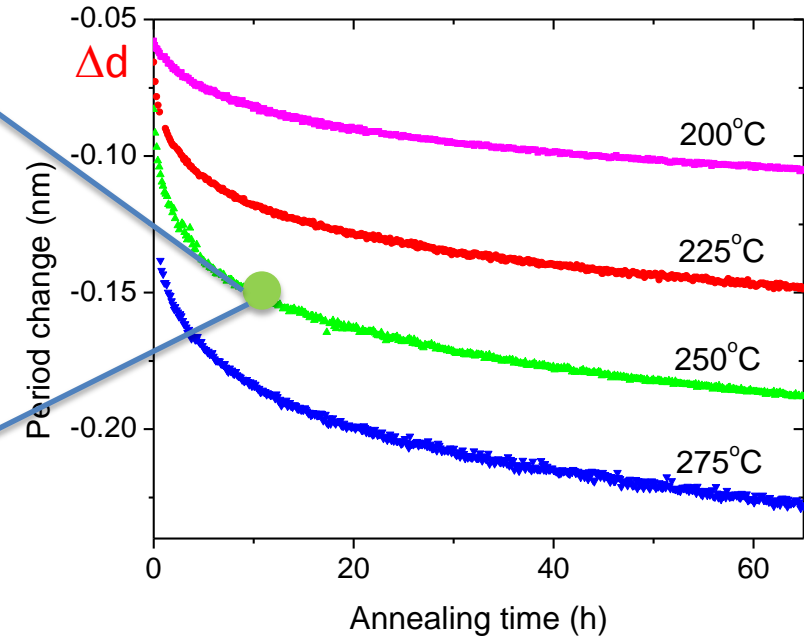
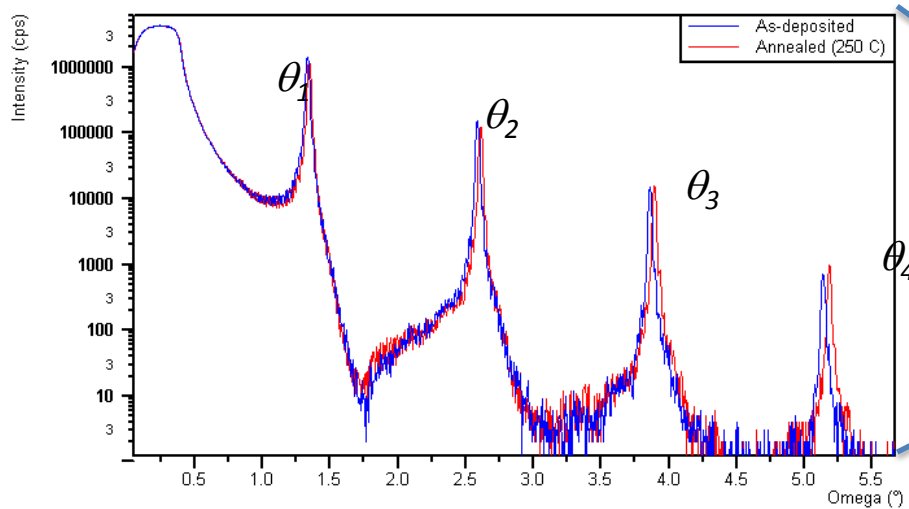
*J. Gaudin et al.,
Opt. Exp. 19 p.15516 (2011)

Beyond ms time scale



Atomic diffusion induced silicide formation

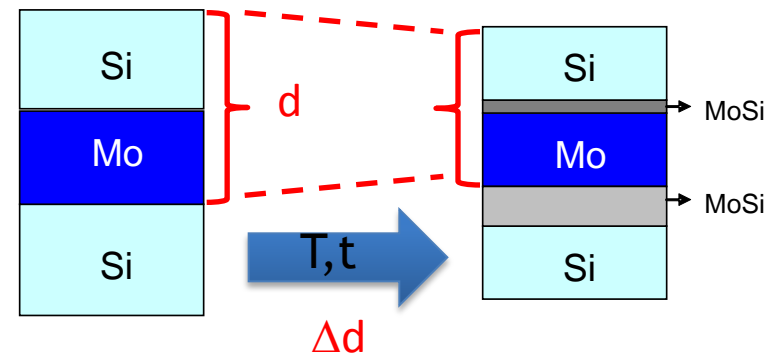
High res. Cu-K_α reflectance , 10h @ 250C



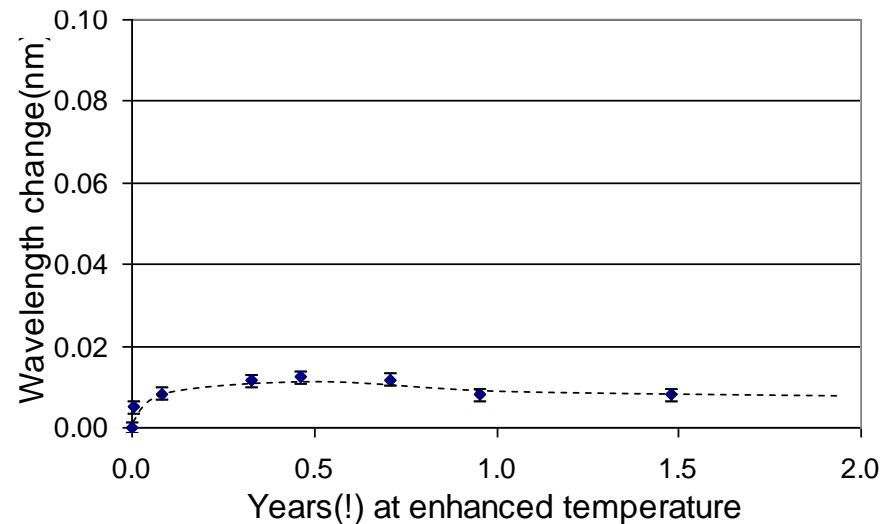
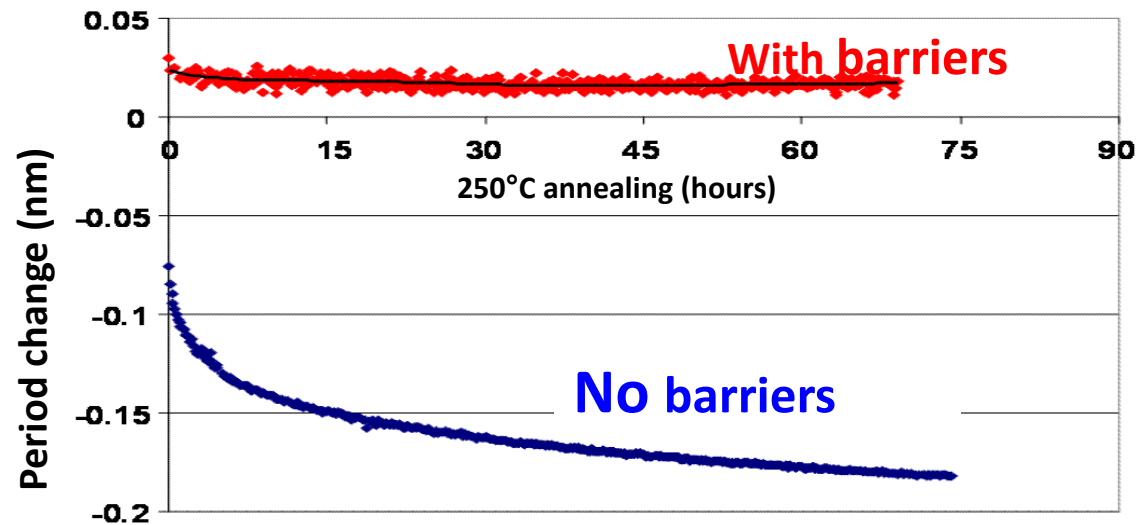
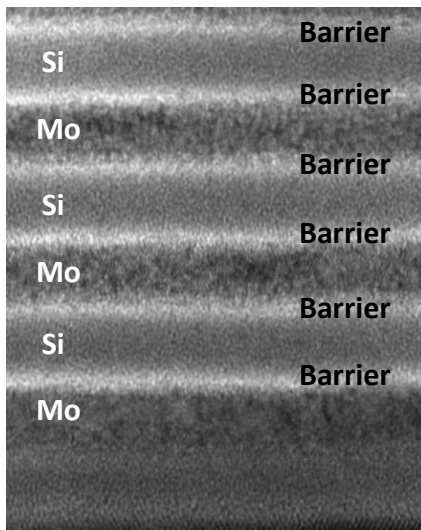
Bragg law:

$$m\lambda = 2d \sin \theta_m \sqrt{1 - \frac{2\bar{\delta}}{\sin^2 \theta_m}}$$

Growth of high density Mo_xSi_y interfaces causes reduction of multilayer period

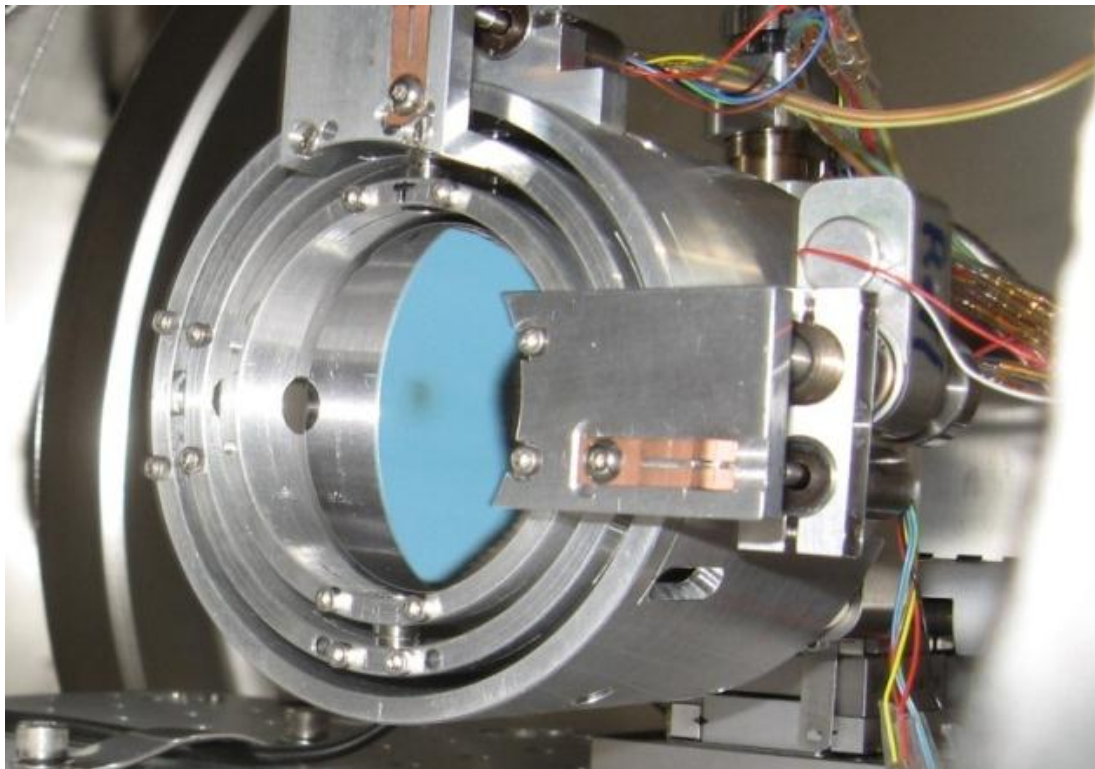


Thermally stable multilayer



„Standard damage” processes

Surface contamination @ FLASH





IP PAS: R. Sobierajski, P. Dłużewski, M. Jurek, M. Klepka, D.Klinger, J.B. Pelka, W. Szuszkiewicz, D.Żymierska



WUT: D.Sobota, W. Wierzchowski, T. Płociński

IP ASCR: L. Juha, J. Chalupsky, V.Hajkova, T. Burian



HASYLAB: N. Stojanovic,

K. Tiedtke S. Toleikis H. Wabnitz

Uni. Essen: K. Sokolowski-Tinten,



LAC: J. Krzywinski, J. Bozek, M. Messerschmidt



LLNL: S. Hau-Riege, R. London



XFEL: J. Gaudin, H.Sinn

FOM: R.A. Loch, E. Louis, S. Bruijn, A.R. Khorsand, R.W. E. van de Kruijs,



SPRING-8: M.Yabashi, M.Nagasono

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